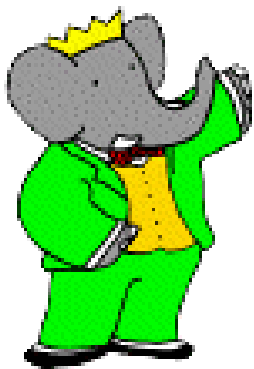


The BaBar Silicon Vertex Tracker (SVT)



BABAR™

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University of California
Santa Barbara

Outline

- Requirements
- Detector Description
- Performance
- Radiation

SVT Design Requirements and Constraints (from TDR)

Performance Requirements

- Δz resolution < 130 mm
- Single vertex resolution < 80 mm.
- Stand-alone tracking for $P_T < 100$ MeV/c.

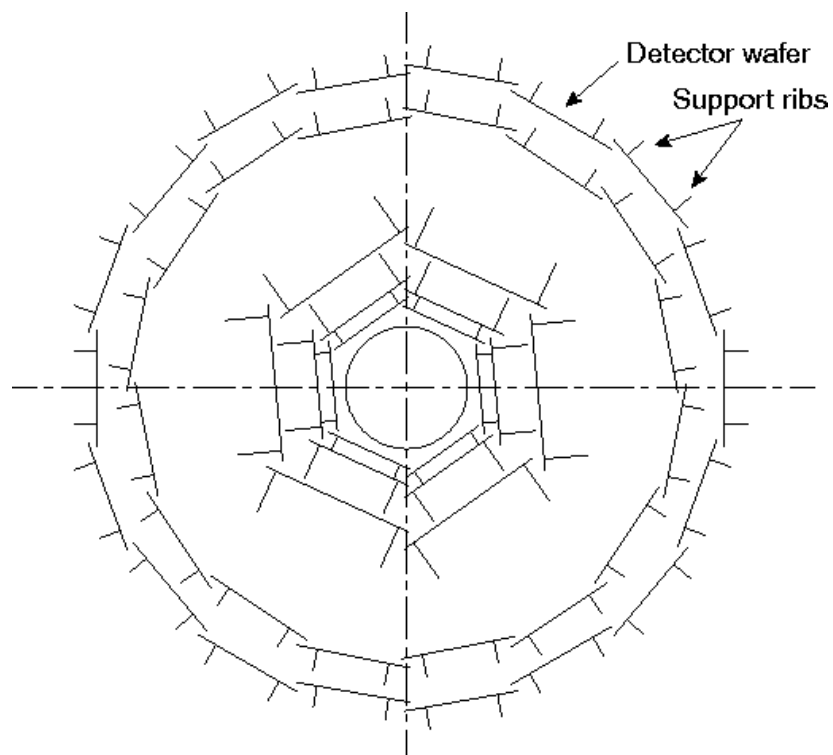
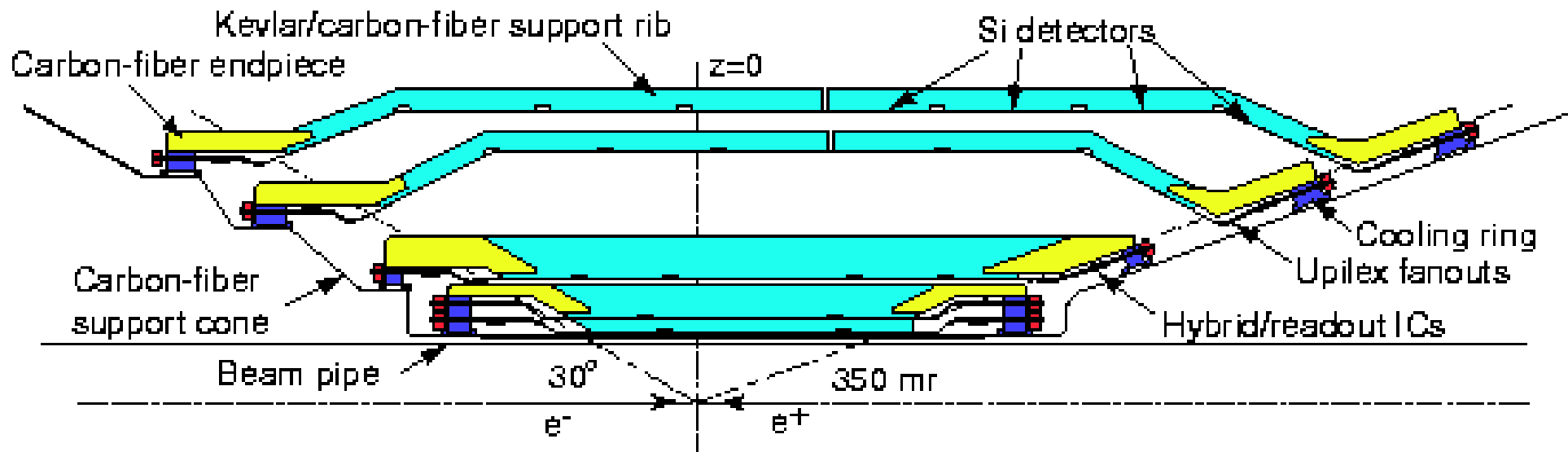
PEP-II Constraints

- Permanent dipole (B1) magnets at ± 20 cm from IP.
 - Polar angle restriction: $17.2^\circ < \Theta < 150^\circ$.
 - Must be clam-shelled into place after installation of B1 magnets
- Bunch crossing period: 4.2 ns (nearly continuous interactions).
- Radiation exposure at innermost layer (nominal background level):
 - Average: 33 kRad/year.
 - In beam plane: 240 kRad/year.
- SVT is designed to function in up to 10 X nominal background.

SVT characteristics

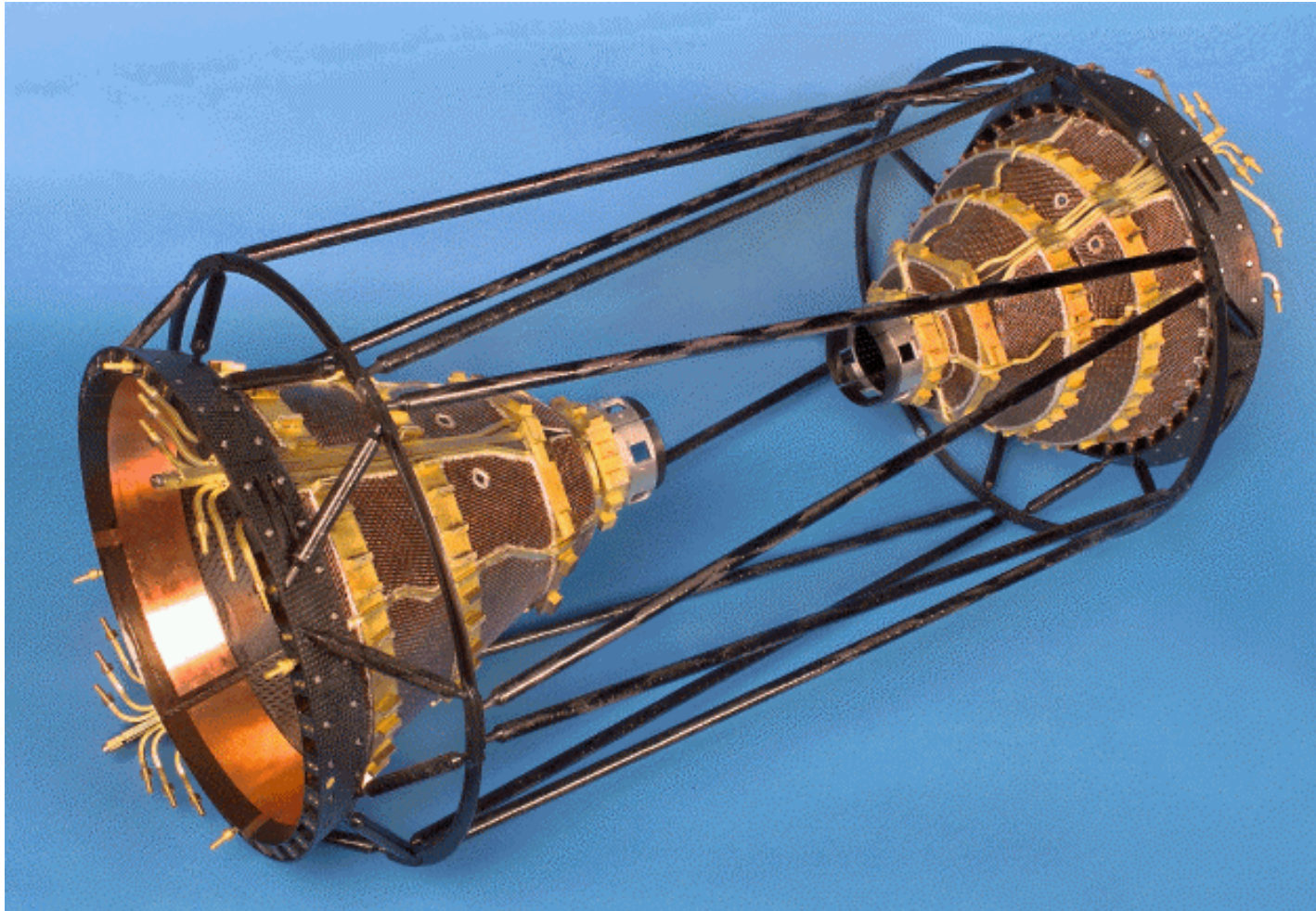
- Five layers, double sided
 - Barrel design, L4 and 5 not cylindrical
 - 340 wafers, 6 different types
 - Low mass Kevlar-Carbon Fiber support ribs
- Upilex fanouts to route signal to ends
- Double-sided AlN HDI (104 of these)
 - Outside tracking volume
 - Mounted on Carbon Fiber cones (on B1 magnets)
- Atom chips
 - 1156 chips, 140K channels

BaBar Silicon Vertex Tracker



Layer	Radius (mm)	Modules/ Layer	Wafers/ Module	F Pitch (mm)	Z Pitch (mm)
1	32	6	4	50 or 100	100
2	40	6	4	55 or 110	100
3	54	6	6	55 or 110	100
4a	124	8	7	100	210
4b	127	8	7	100	210
5a	140	9	8	100	210
5b	144	9	8	100	210

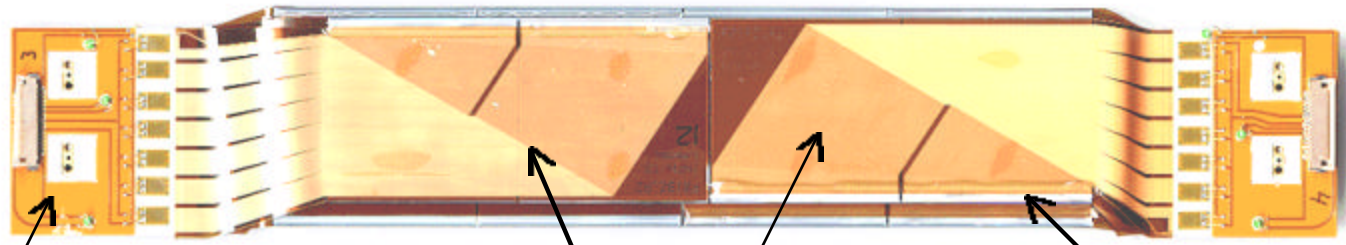
Space Frame and Support Cones...mounted on B1 magnets



SVT Modules

Z-Side

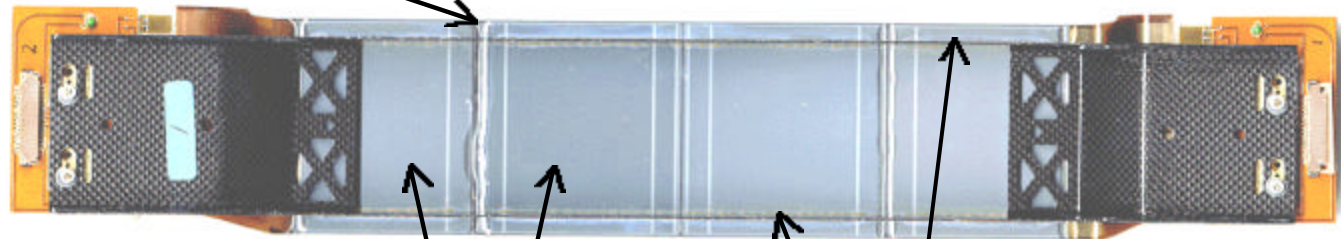
High Density Interconnect
(mechanical model)



Flexible Upilex Fanout

Micro-bonds

Phi-Side



Micro-bonds

Si Wafers

Carbon/Kevlar fiber
Support ribs

Fanout Properties:

- $< 0.03 \% X_0$
- 0.52 pF/cm



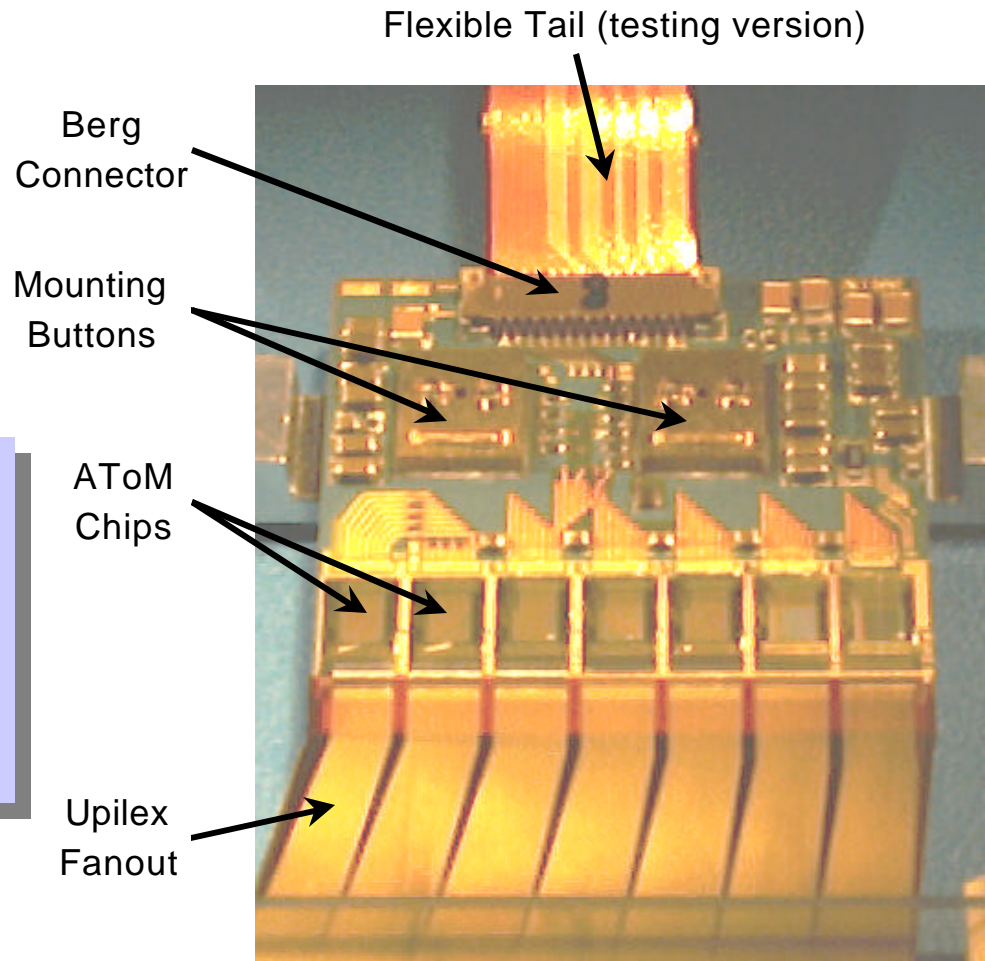
SVT High Density Interconnect

Functions:

- Mounting and cooling for readout ICs.
- Mechanical mounting point for module.

Features:

- AlN substrate.
- Double sided.
- Thermistor for temp. monitor.
- 3 different models.



Silicon Wafers

Features

- Manufactured at Micron.
- 300 μm thick.
- 6 different wafer designs.
- n⁻ bulk, 4-8 $\text{k}\Omega\text{ cm}$.
- AC coupling to strip implants.
- Polysilicon Bias resistors on wafer, 5 $\text{M}\Omega$.

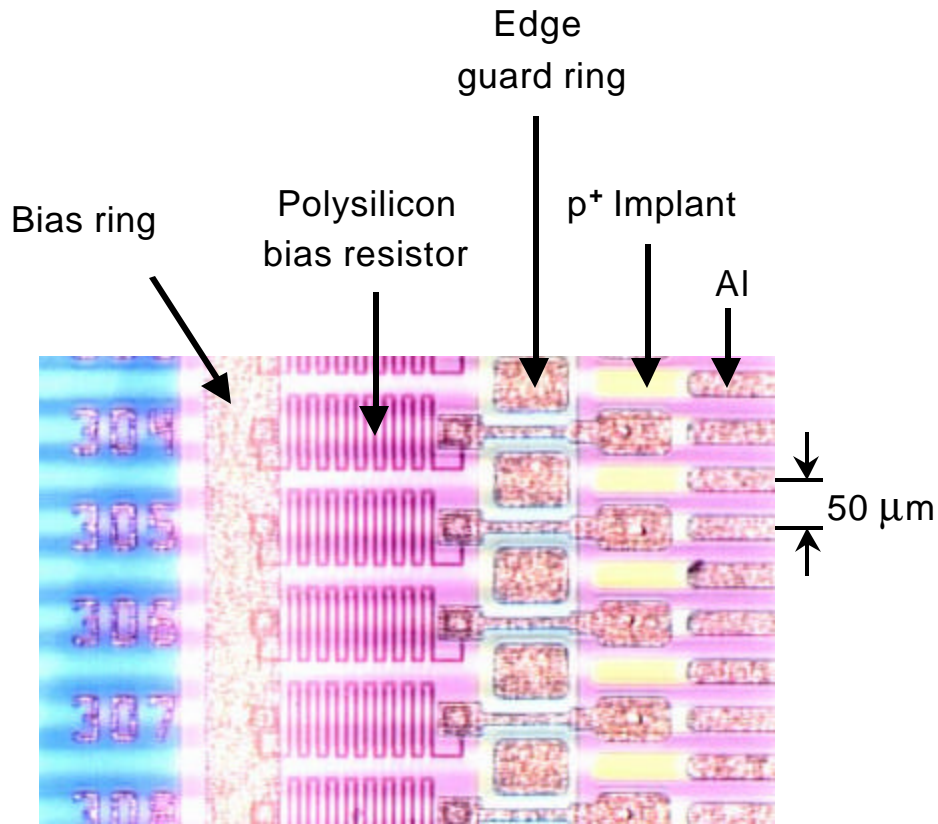
Bulk Properties

- **Bias current:** 0.1 to 2.0 μA
- **Bulk current:** 0.1 to 2.0 μA
- **Depletion voltage:** 10 to 45 V

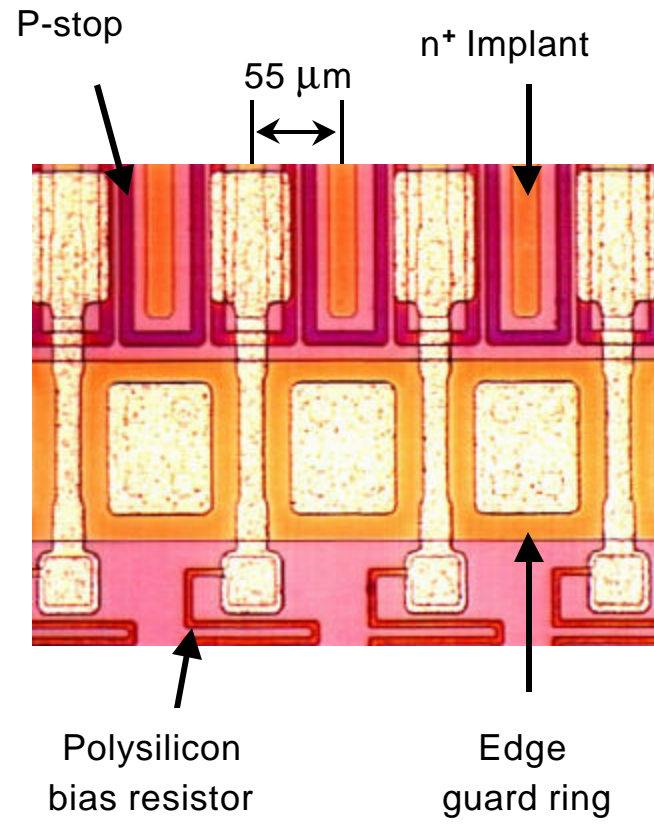
Strip Properties

	<u>n-side</u>	<u>n-side</u>	<u>n-side</u>	<u>p-side</u>
• Strip Pitch:	50 μm	55 μm	105 μm	50 μm
• Inter-strip C:	1.1 pF/cm	1.0 pF/cm	1.0 pF/cm	1.1 pF/cm
• AC decoupling C:	20 pF/cm	22 pF/cm	34 pF/cm	43 pF/cm
• Implant-to-back C:		0.19 pF/cm	0.36 pF/cm	0.17 pF/cm
• Bias R:	4 to 8 $\text{M}\Omega$	4 to 8 $\text{M}\Omega$	4 to 8 $\text{M}\Omega$	4 to 8 $\text{M}\Omega$

Silicon Wafers



p⁺ strip side



n⁺ strip side

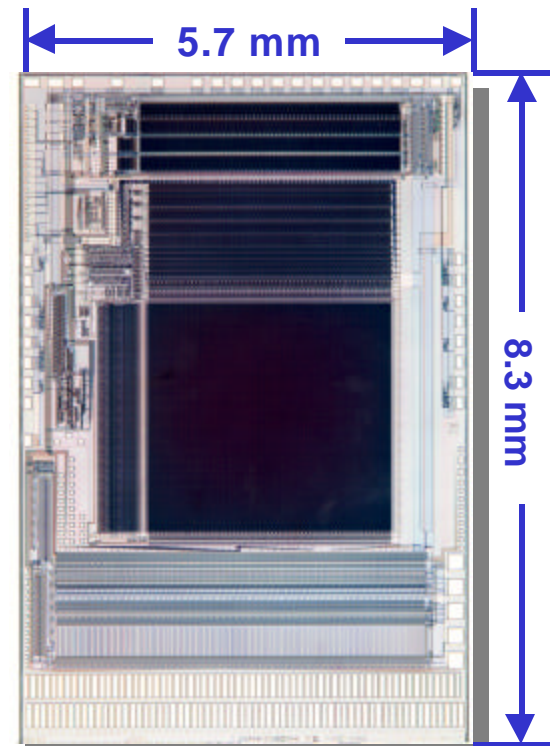
The AToM Chip

Custom Si readout IC

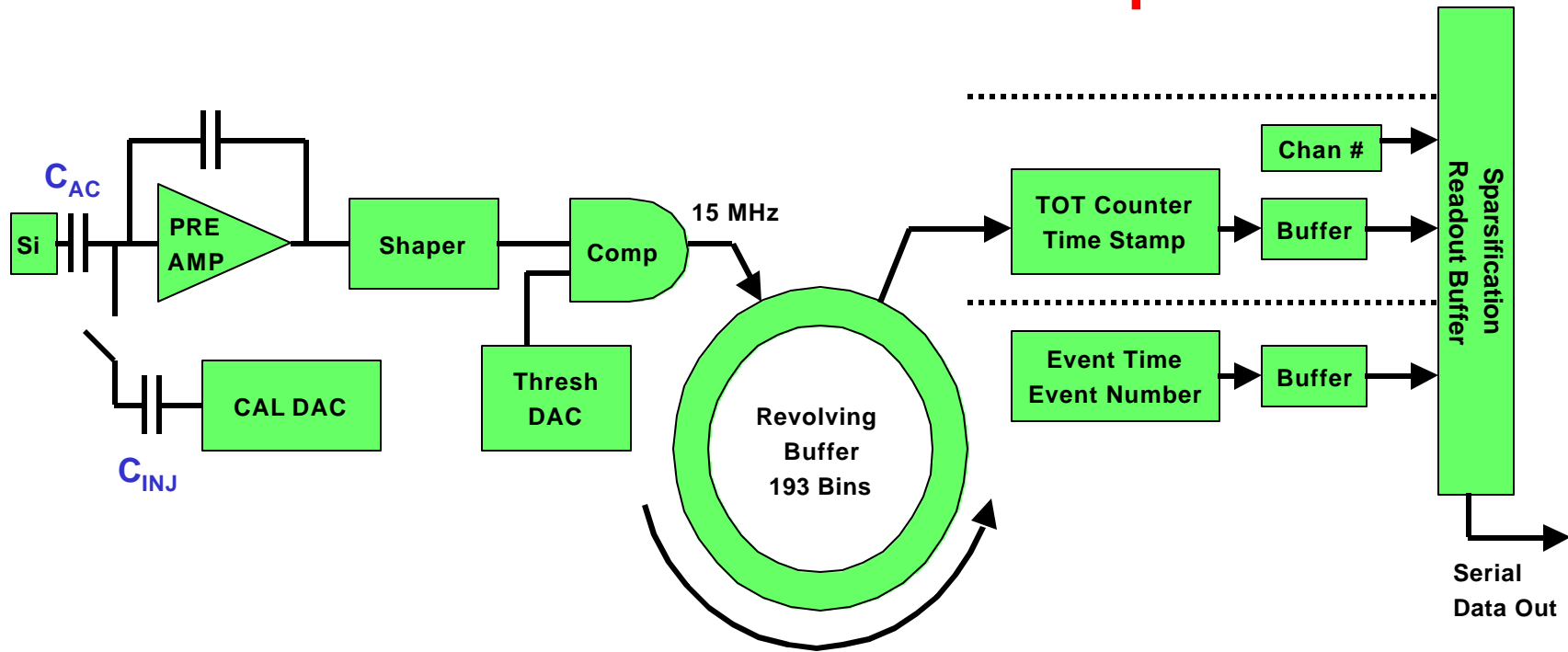
AToM = **A** **T**ime **O**ver threshold **M**achine

Features:

- 128 Channels per chip
- Rad-Hard CMOS process (Honeywell)
- Simultaneous
 - Acquisition
 - Digitization
 - Readout
- Sparsified readout
- Time Over Threshold (TOT) readout
- Internal charge injection



The AToM Chip



Amp. Shape, Discr. Calib

- 5-bit CAL DAC (0.5 fC/count)
- 5-bit Thr DAC (0.05 fC/count)
- Shaping time 100 - 400 ns
- Typical threshold 0.6-0.9 fC

Trigger Latency Buffer

- 15 MHz Sample rate
- Total storage = 12.7 μ s

TOT, Tstamp, Buffering

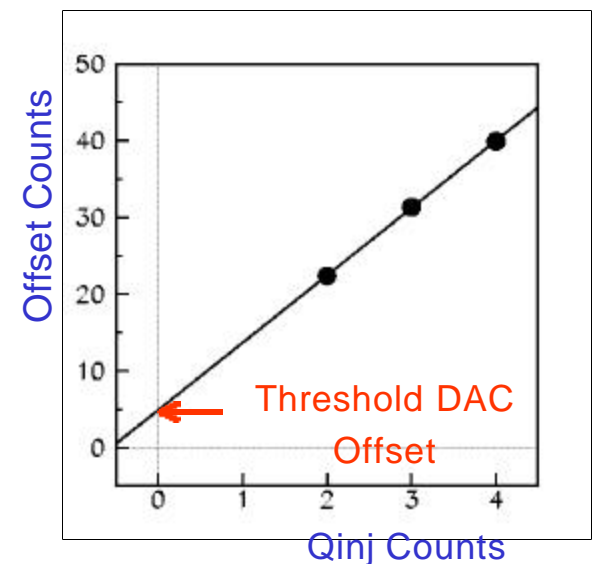
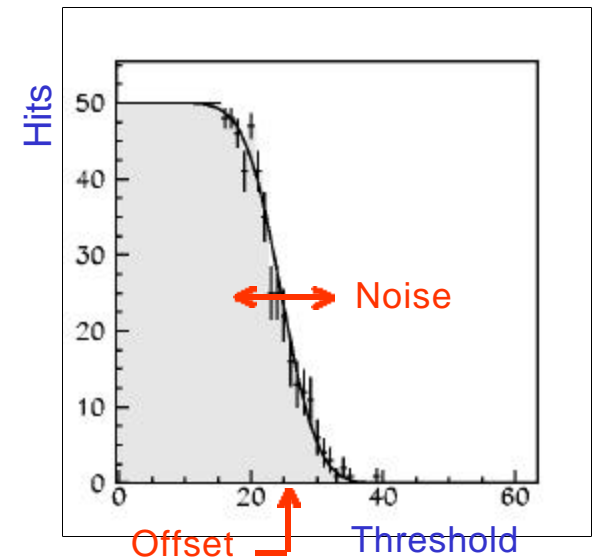
- 4 bits TOT (logarithmic)
- 5 bits Hit Tstamp (67 ns/count)
- 4 buffers / channel

Performance

- Calibration, Noise
- Occupancy
- Efficiency
- Intrinsic Resolution

Calibration

- Noise, gain, pedestals, bad channels obtained from scanning threshold with and without charge injection and counting hits
 - 600K errfun fits, 150K linear fits
 - once a day; takes ~ 2 minutes
- Very stable
- Downloadable chip parameters have not changed since Oct 1999

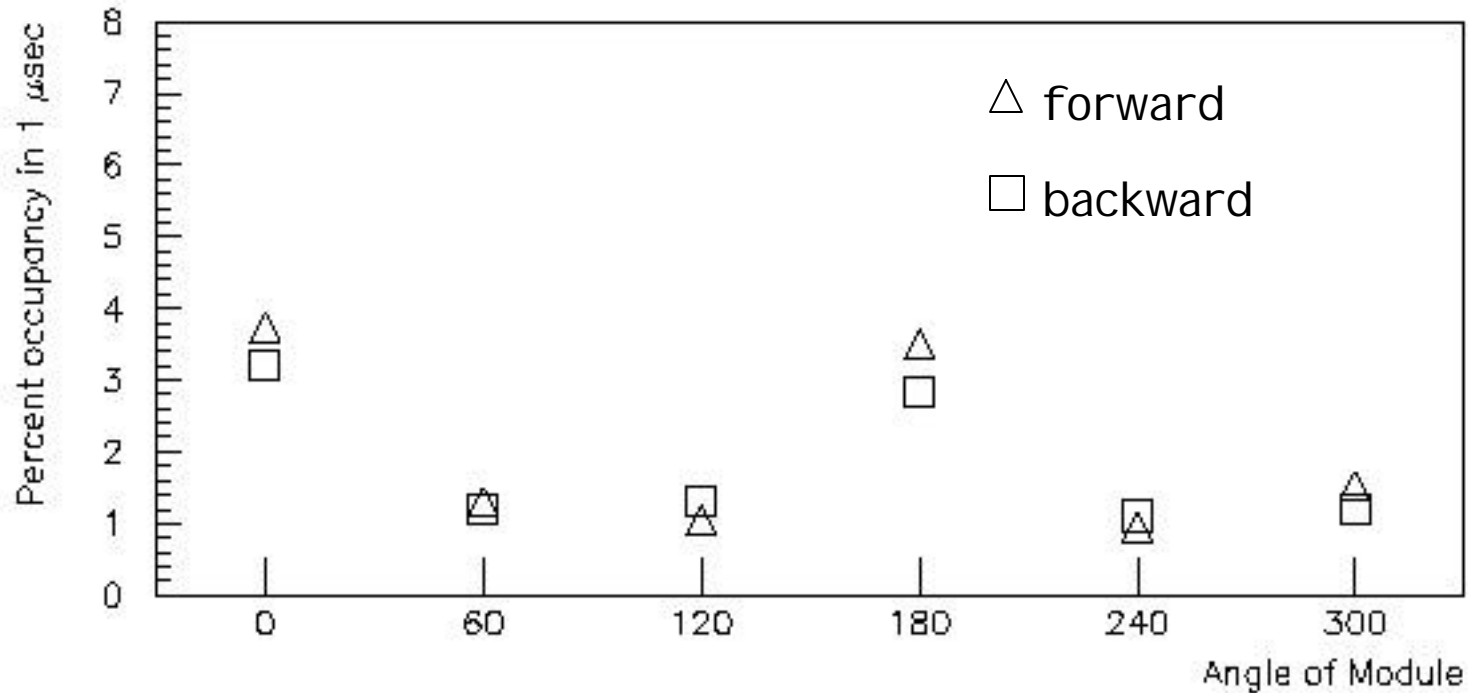


Noise

Layer	ENC	Layer	ENC
1 ϕ	1200	1z	880
2 ϕ	1240	2z	970
3 ϕ	1440	3z	1180
4 ϕ	1350	4z	1210
5 ϕ	1600	5z	1200

1 MIP at normal incidence, about 23,000 electrons

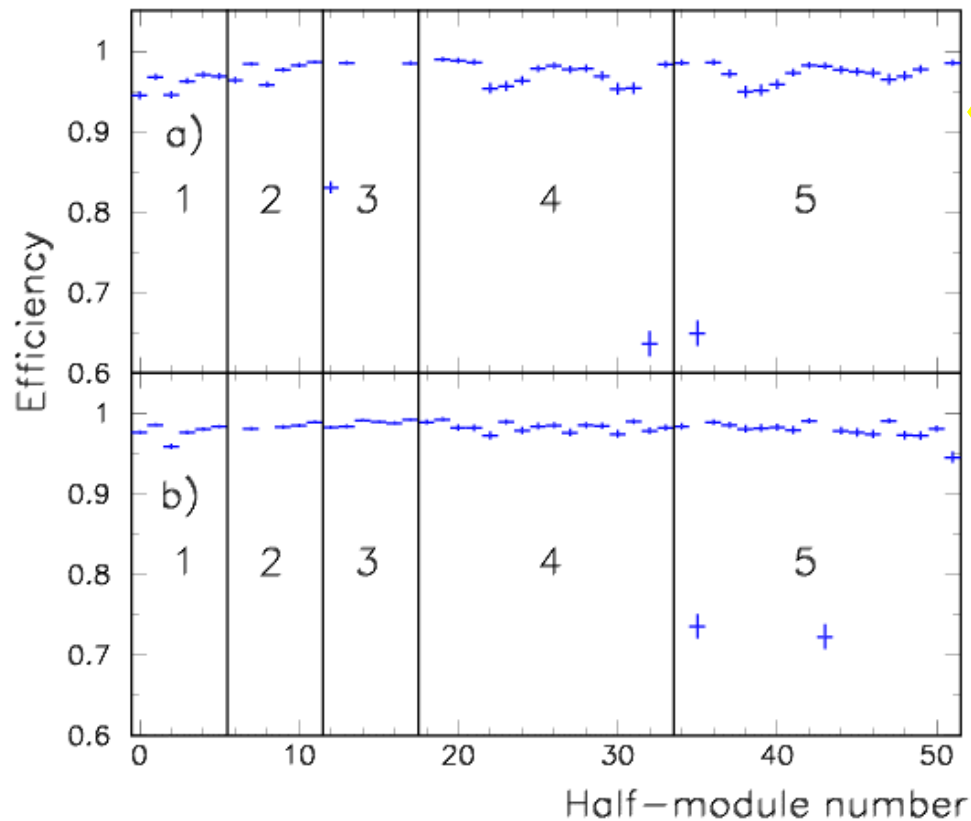
Occupancy (Layer 1)



Offline $\Delta t \sim 300$ nsec

→ effective occupancy lower by factor ~ 3

Cluster efficiency

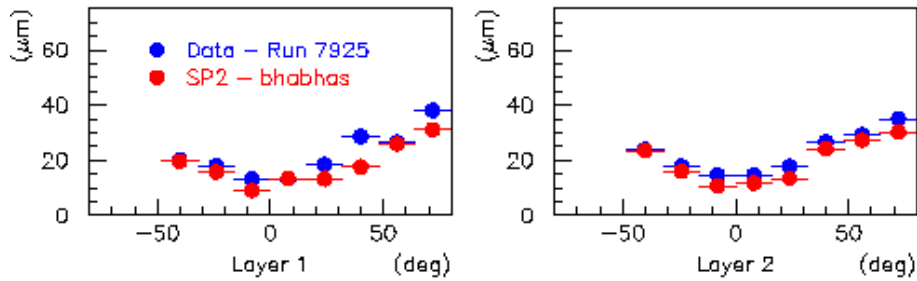


$\epsilon \sim 97\%$
(SW + HW)

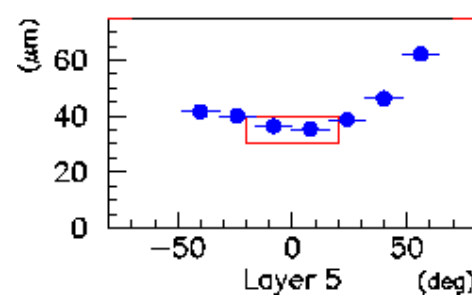
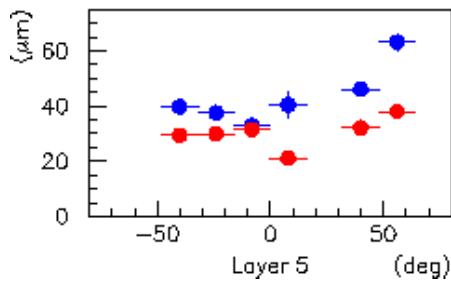
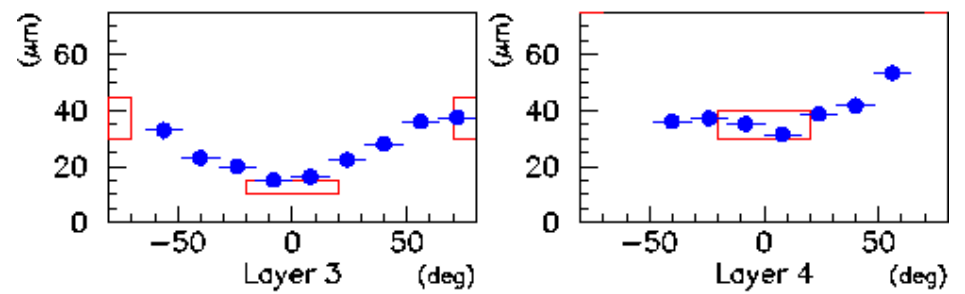
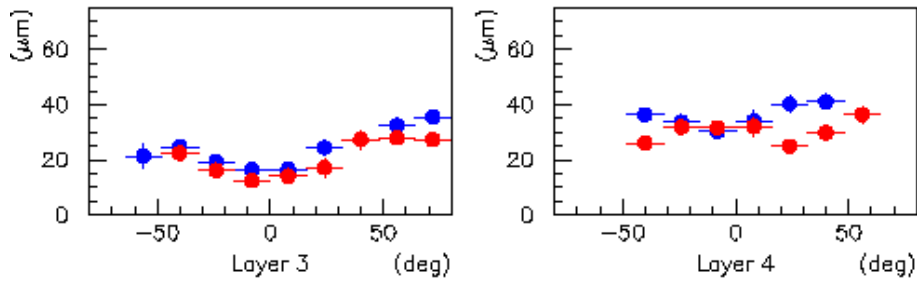
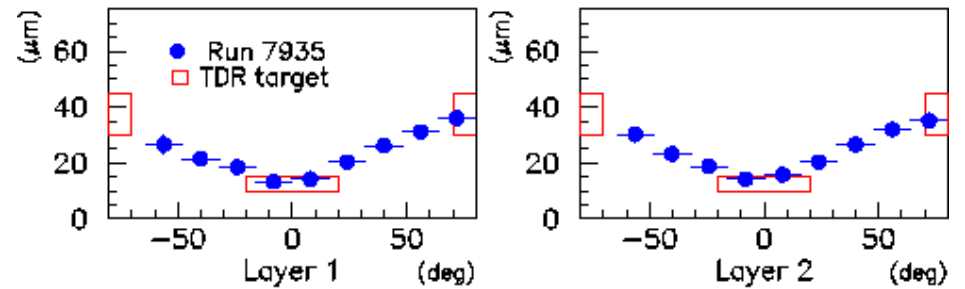
Excluding 9/208
malfunctioning readout sections

Resolution

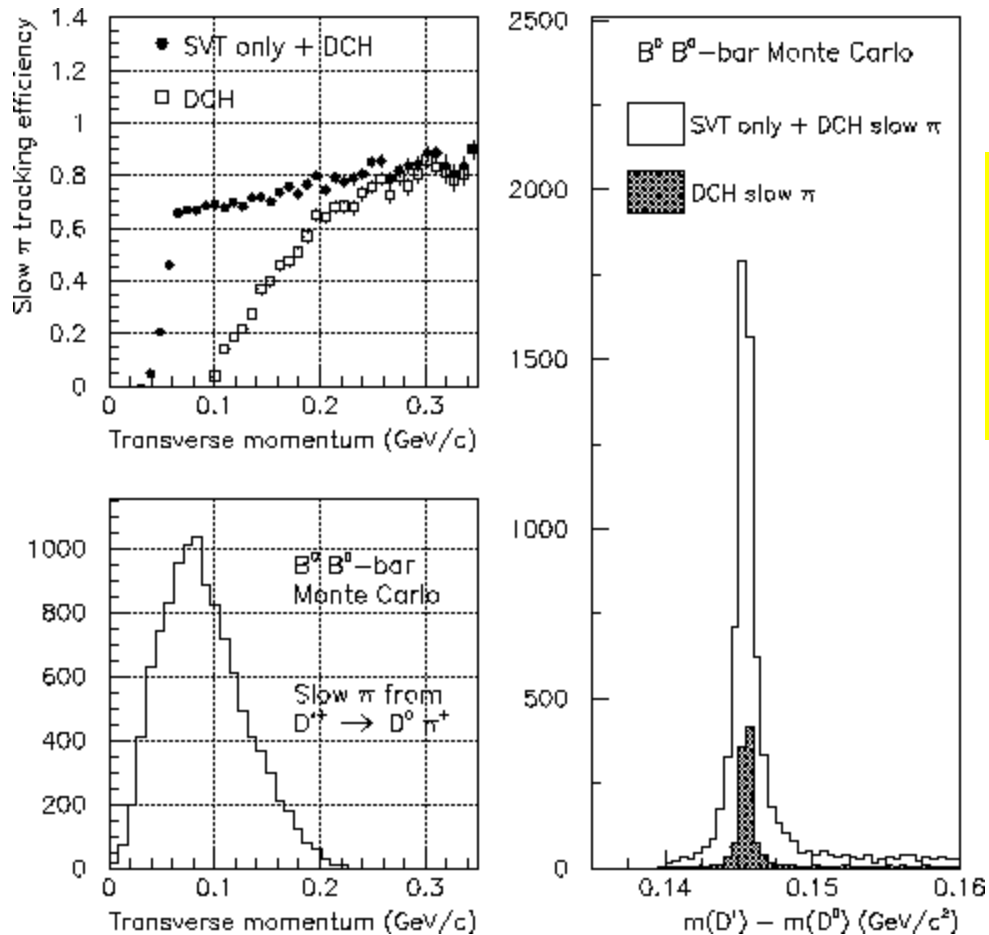
Resolution vs projected angle -Zed



SVT Hit Resolution vs Angle - Zed View



Standalone reconstruction of low P_T tracks



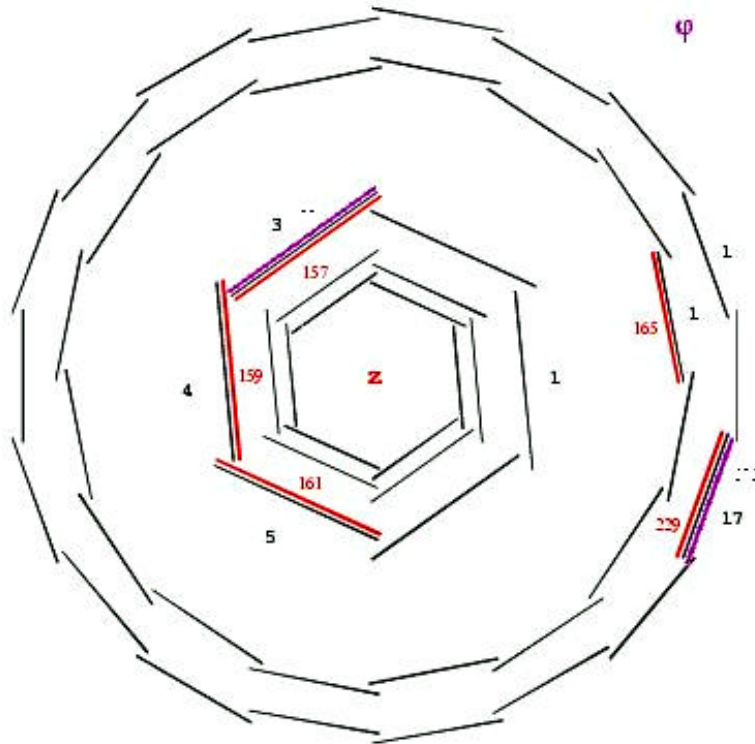
Reconstruction of π_S from
 $D^* \rightarrow D \pi_S$
is (mostly) with SVT alone

Map of malfunctioning modules (9/208)

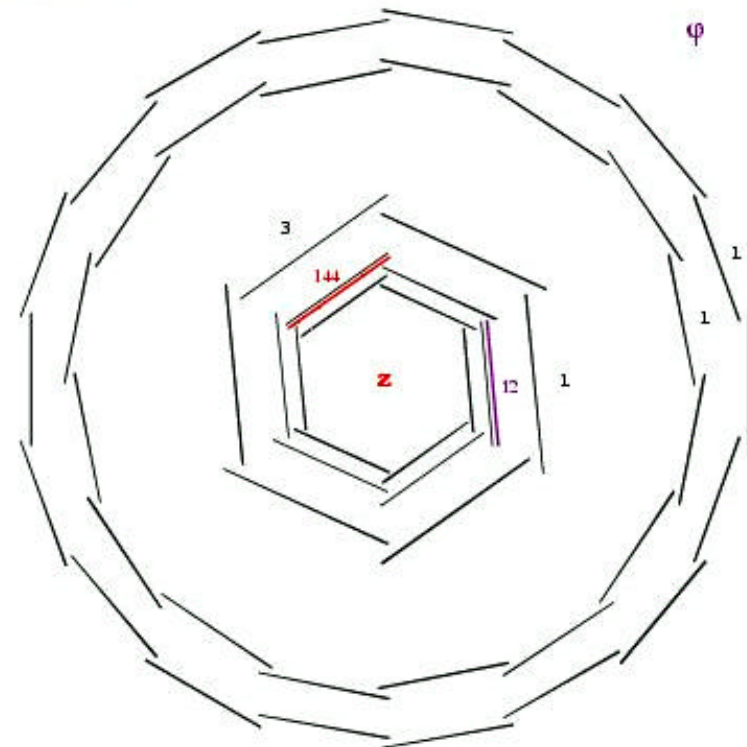
- Layer 1 perfect
- Problems are from
 - shorts on hybrids
 - elec. problems on wafers
 - slipped out cables

—— Bad ϕ
—— Bad z

FORWARD

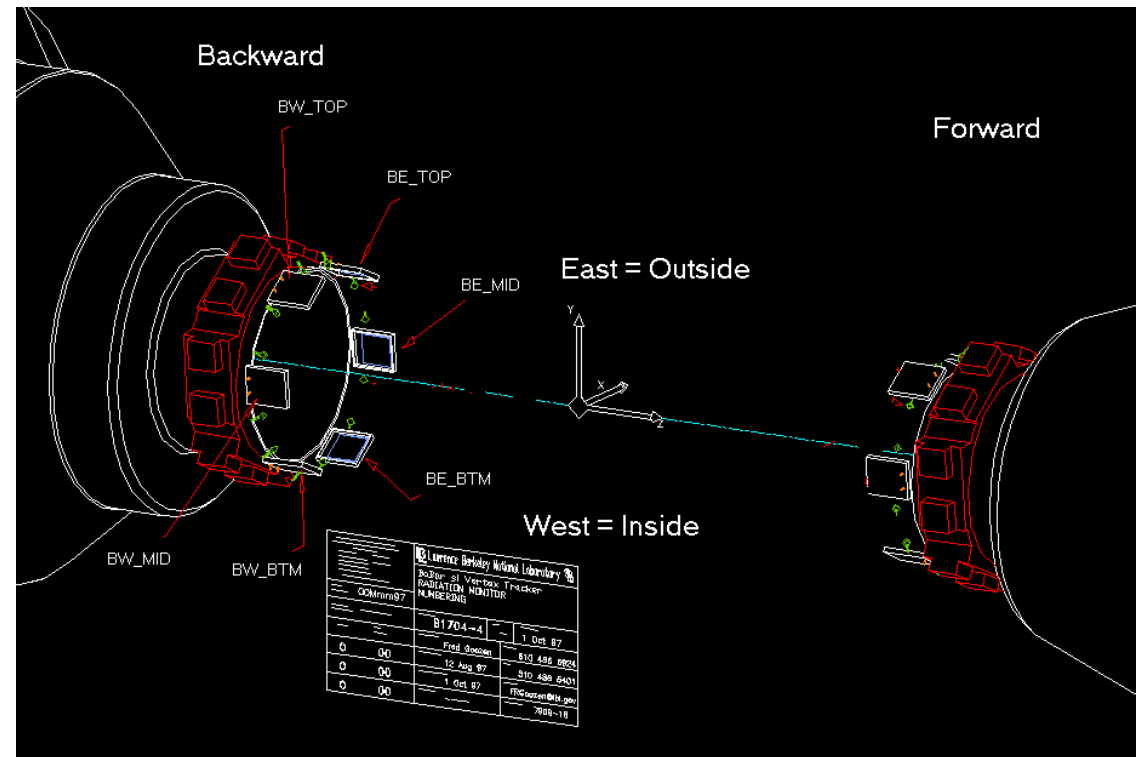


BACKWARD



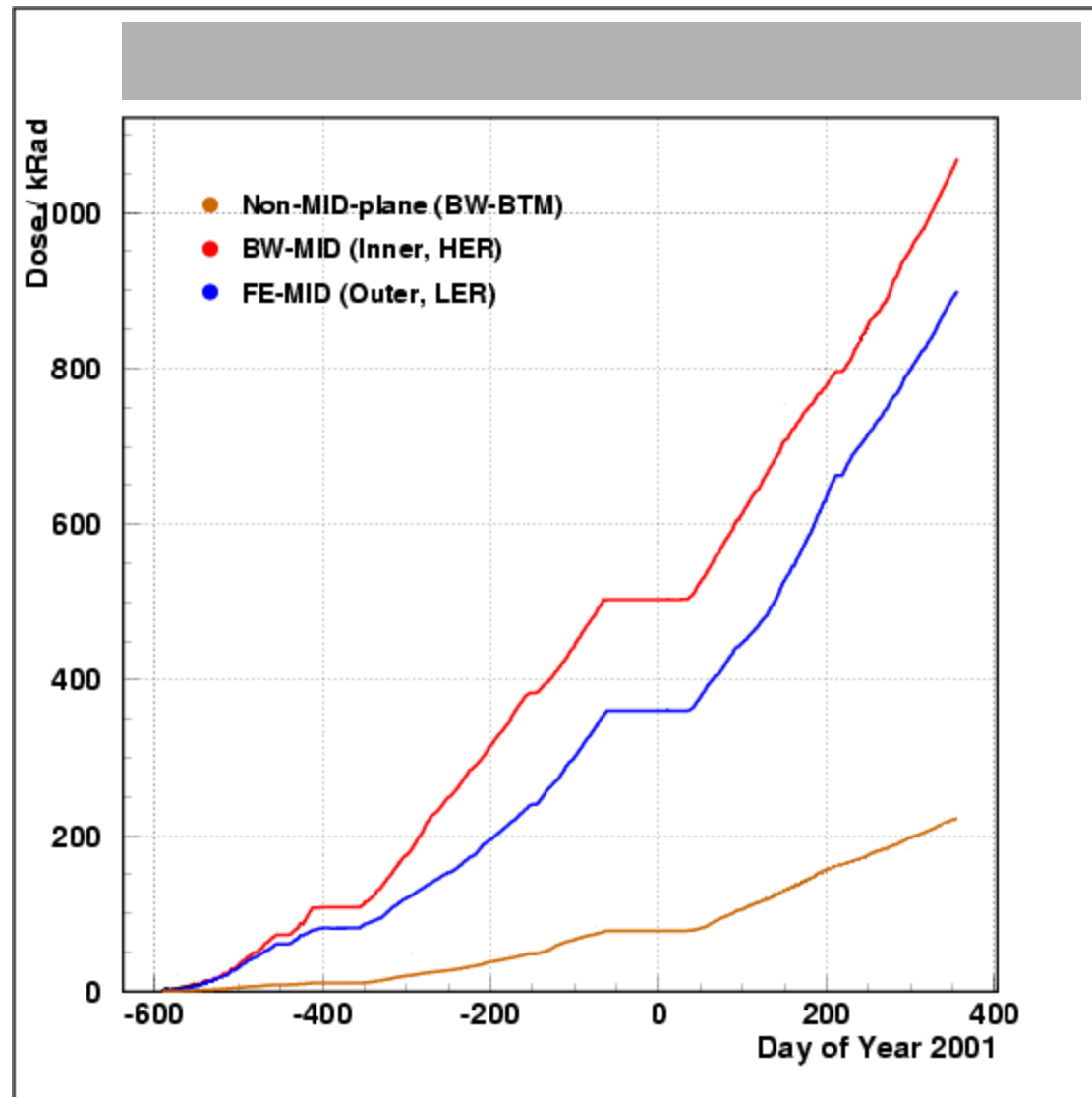
Radiation

- Monitored by 12 diodes at ~ radius of layer 1
- Diodes can abort beam
- Operation tricky due to heavy radiation damage



SVTRAD System

Measured absorbed Dose



Projected absorbed dose, midplane

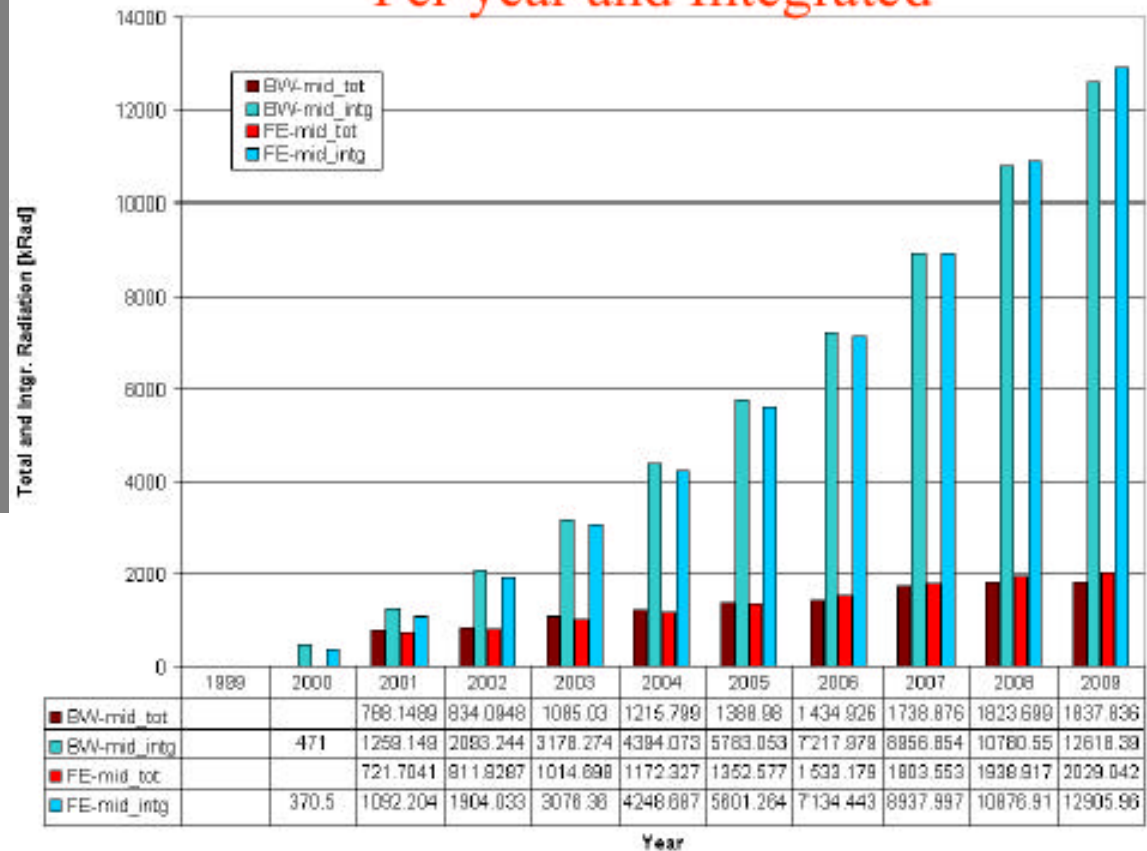
Based on PEP II current profile and measured dose/current

Includes injection, etc

A bit conservative....

Off-midplane ~ x5 lower

Per year and Integrated

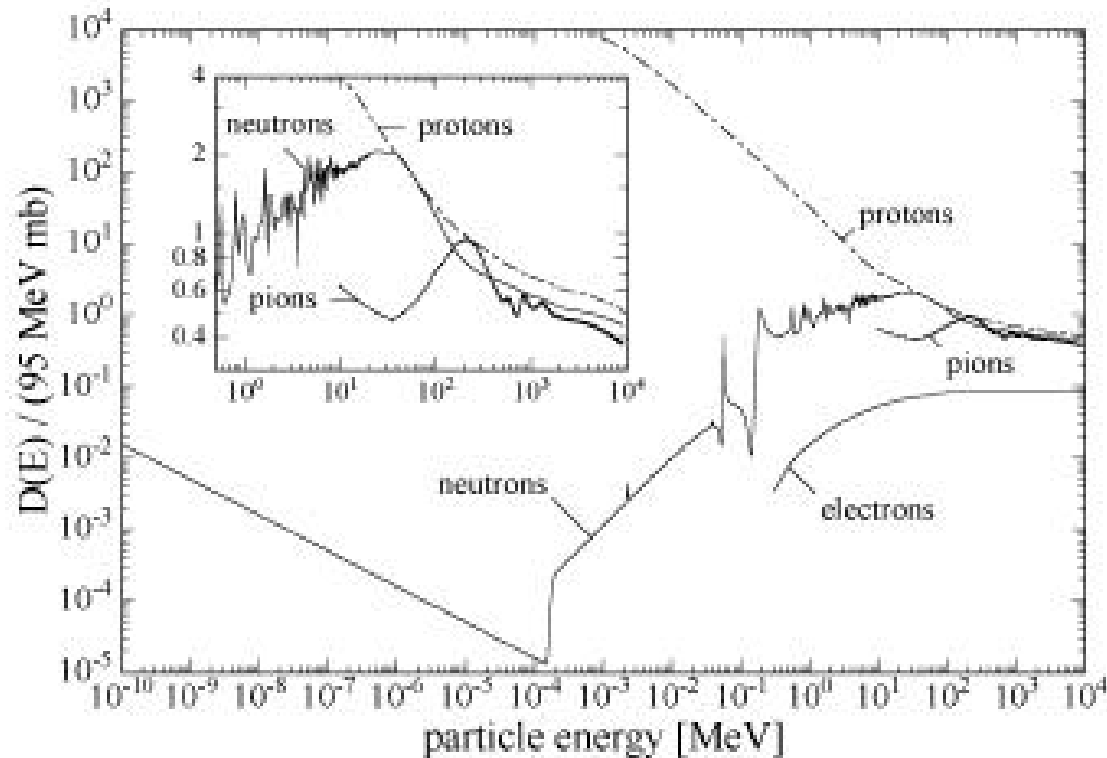


Consequences of high doses

- Bulk damage to Si
 - increase I_{LEAK} → increase in noise
 - not a real problem until very high doses
 - type inversion
- Damage to chips
 - originally tested (fully) only to 2 MRad
 - test to higher doses

Bulk Damage

~ Damage effectiveness →



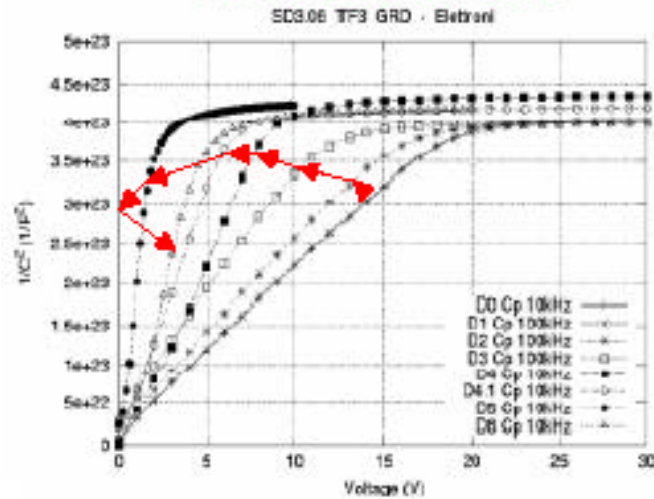
from Moll

NI EL scaling: high energy electron cause significant damage (~1/10 of hadrons)

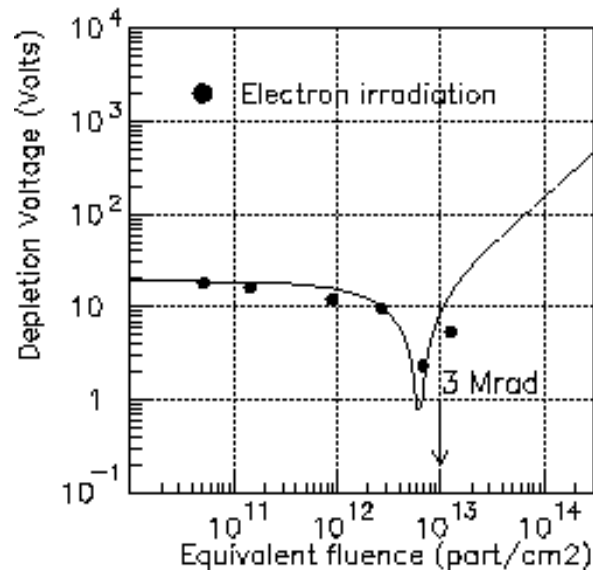
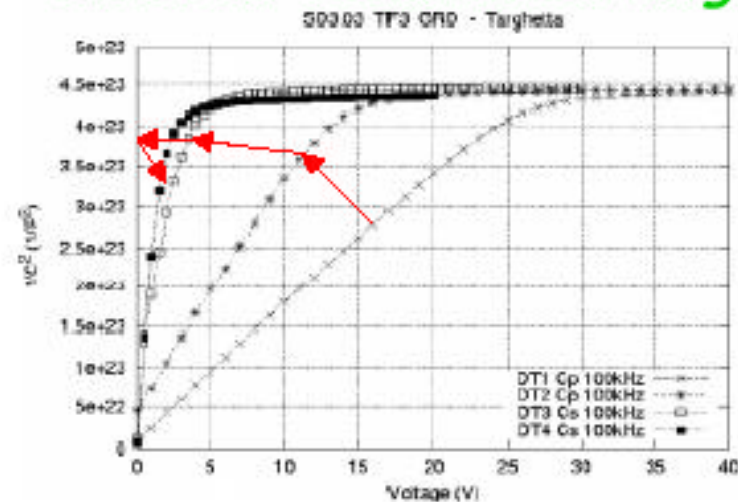
Not appreciated by us until recently

Tests at Elettra (Trieste)

electron beam



electron beam on Cu target

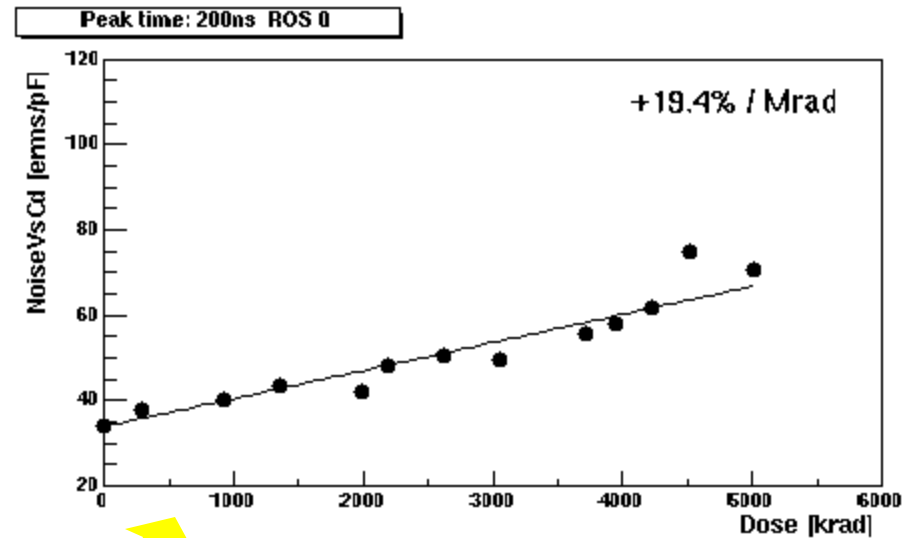
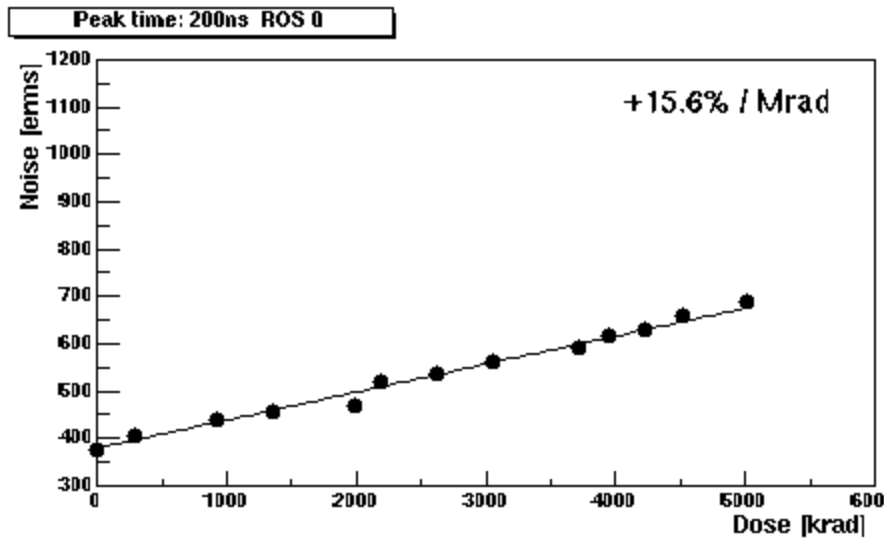


- C^{-2} vs V curve show inversion
- Results in \sim agreement with NI EL scaling hypothesis
- Leakage current increase of order $2 \mu\text{A}/\text{cm}^2$
 - agrees with in-situ measurement

Detector Radiation Tests (Cont.)

- Electrical properties after inversion:
 - Strip isolation OK
 - Edge currents, no sudden increase, manageable
 - Still to do: test of charge-collection efficiency
 - According to literature, should be OK
- sensors OK to at least 5-6 MRad

AtoM tests beyond 2MRad



$$\text{Noise} = \alpha + \beta C_{\text{Load}}$$

Significant increase in noise but chip functions to at least 5 MRad

SVT Module Replacement

- Summer 04 shutdown: replace
 - L1/2 midplane modules
 - worst case dose by then ~ 3.5 MRad
 - other malfunctioning modules
- New modules identical to existing ones
- New modules under construction now

Conclusion

- The BaBar SVT is working well
 - efficient
 - resolution according to spec
 - standalone tracking
- Replace radiation damaged modules in 04
- Extend lifetime to ~ 07
- After that ?
 - depends on many things (machine, physics etc.)